

IPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Re the Application of
Hiromi OTOMA

Group Art Unit: 2828

Application No.: 10/826,354

Filed: April 19, 2004

Docket No.: 119498

For: SURFACE EMITTING SEMICONDUCTOR LASER AND COMMUNICATION SYSTEM
USING THE SAME

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. Relevance of the non-English language references 1-7 is discussed in the present specification.
- 3. An English-language Abstract of the non-English language reference 1 is attached hereto.
- 4. A computer-generated English translation of the following Japanese reference has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See Reference 1.

Respectfully submitted,


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JAO:TJP/mlo
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| DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461 |
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Sheet 1 of 1

| Form PTO-1449 (REV. 8-83) | | US Dept. of Commerce PATENT & TRADEMARK OFFICE | | ATTY DOCKET NO. 119498 | APPLICATION NO. 10/826,354 | |
|---|----|--|-----------|-------------------------------|-------------------------------|-----------|
| INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | | | | APPLICANT Hiromi OTOMA | | |
| | | | | FILING DATE April 19, 2004 | GROUP 2828 | |
| U.S. PATENT DOCUMENTS | | | | | | |
| EXAMINER INITIAL | | DOCUMENT NUMBER | DATE | NAME | CLASS | SUB CLASS |
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| FOREIGN PATENT DOCUMENTS | | | | | | |
| | | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUB CLASS |
| | 1. | JP A 2002-185079 w/abstract & transl. | 6/28/2002 | JAPAN | | |
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| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.) | | | | | | |
| | 2. | Kenichi IGA; "Surface Emitting Laser"; IEICE Transactions C-1, Vol. J81-C-1, No. 9; September 1998; pp 483-493 | | | | |
| | 3. | H. OTOMA et al.; "Fabrication and Performance of 12 X 12 Matrix-Addressed 780nm Oxide-Confining Vcsel Array"; Bulletin of Solid State Physics and Applications; Vol. 5, No. 1.; 1999; pp 11-15 | | | | |
| | 4. | Nobuaki UEKI et al.; "Single-Transverse-Mode 3.4-mW Emission of Oxide-confined 780-nm Vcsel's"; IEEE Photonics Technology Letters; Vol. 11, No. 12; December 1999; pp 1539-1541 | | | | |
| | 5. | Jun SAKURAI et al.; "10 Gb/s Surface Emission Semiconductor Laser"; Electronic Materials, Vol. 41, No. 11; November 2002; pp 49-52 | | | | |
| | 6. | M. Grabherr et al.; "Efficient Single-Mode Oxide-Confining GaAs VCSEL's Emitting in the 850-nm Wavelength Regime"; IEEE Photonics Technology Letters; Vol. 9, No. 10; October 1997; pp 1304-1306 | | | | |
| | 7. | Aaron et al.; "Aperture Placement Effects in Oxide-Defined Vertical-Cavity Surface-Emitting Lasers"; IEEE Photonics Technology Letters; Vol. 10, No. 10; October 1998; pp 1362-1364 | | | | |
| EXAMINER | | | | DATE CONSIDERED | | |
| Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | |